

ArF Immersion Scanner





Ultra-high throughput with enhanced overlay accuracy

The NSR-S622D ArF immersion scanner was developed for high-volume multiple patterning applications at the sub-20 nm generation through further enhancements to the accuracy and productivity of the proven Streamlign Platform. The S622D builds upon S621D Streamlign technology, and delivers crucial enhancements to mix-and-match overlay (MMO) through improvements in lens performance and the autofocus mechanism. The S622D delivers ultra-high productivity with throughput greater than 200 wafers per hour and MMO that is NSR-S622

3.5 nm or less, to support chip makers' cutting-edge production lines.

Performance	
Resolution	≦ 38 nm
NA	1.35
Exposure light source	ArF excimer laser (193 nm wavelength)
Reduction ratio	1:4
Maximum exposure field	26 mm × 33 mm
Overlay	\leq 2 nm (SMO ^{*1}), \leq 3.5 nm (MMO ^{*2})
Throughput	≥ 200 wafers/hour (300 mm wafer, 125 shots)

*1 Single machine overlay: machine-to-self overlay accuracy (NSR-S622D#1 to S622D#1)

*2 Mix and match overlay: machine-to-machine overlay accuracy (NSR-S622D#1 to NSR-S622D#2)

Main Characteristics of the Streamlign Platform

Bird's Eve Control **Enabling superior yield**

- Hybrid encoder/interferometer system delivers optimal stage performance.
- Dramatically improves accuracy and stability.
- Provides superior focus control.
- Overlay capabilities of 2 nm or less

Stream Alignment Enabling optimal affordability

- Straight Line Auto-Focus generates dense map of the wafer surface to enhance focus control (using a wide AF beam span).
- · Enables increased alignment sites with minimal productivity impact using Five-Eye FIA.
- Greatly reduces wafer overhead time.
- Throughput capabilities of 200 WPH or more

Modular² Structure **Enabling rapid production ramps**

- Modular design enables efficient installations and simplifies maintenance.
- Provides optimal uptime with modular design and replacement of individual components.
- Extendible platform enables multigenerational use.

TO ENSURE CORRECT USAGE, READ MANUALS CAREFULLY BEFORE USING YOUR EQUIPMENT.

The export of this product is controlled by Japanese Foreign Exchange and Foreign Trade Law and International export control regime. It shall not be exported without authorization from the appropriate governmental authorities.

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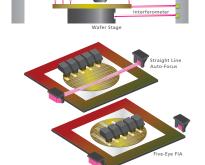
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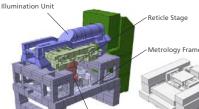
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> ISO 9001 BUREAU VERITAS

This product was developed and manufactured in the factory ce





Wafer Stage

CLASS 1 LASER PRODUCT

Projection Lens

http://www.nikon.co.jp/pec